



Investigation of a Next Generation Piezo Bimorph Mirror

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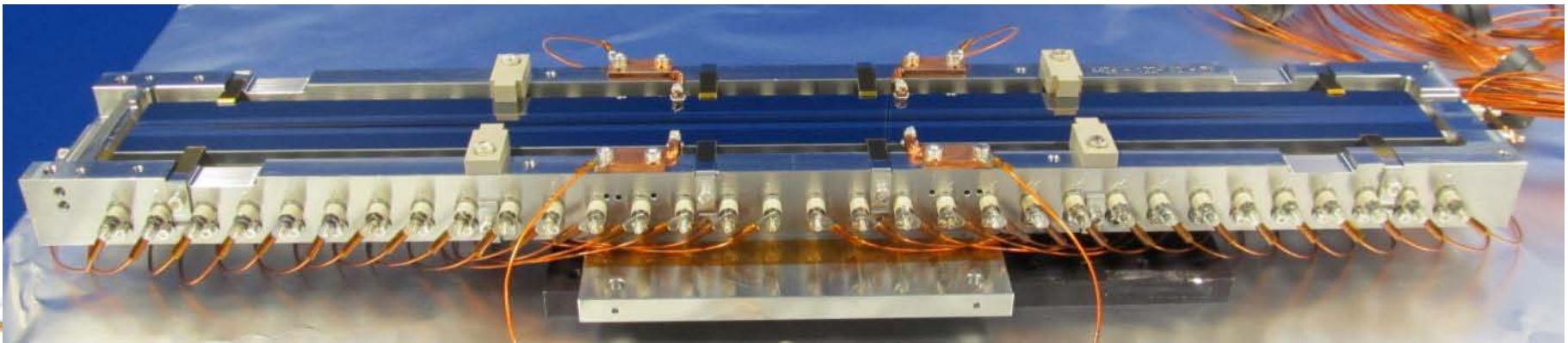
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Advantages of bimorph mirrors

- ☀ Versatility: can be bent to a range of ellipses to provide variable focal distance or X-ray spot size / shape
- ☀ Remove distortions:
 - Polishing
 - Clamping
 - Heat bump
- ☀ Correct wavefront errors introduced by other optics or source

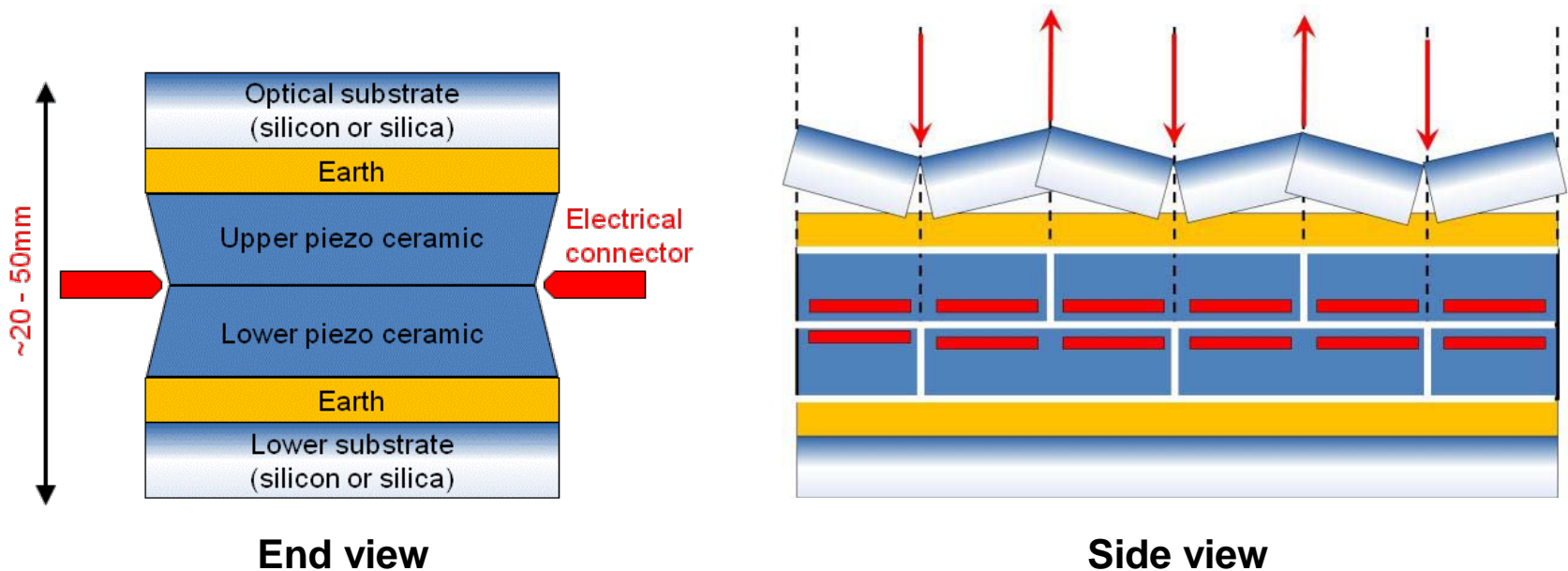


Bimorph control and analysis

- ☀ In-house developed software (EPICS) used routinely at all bimorph beamlines:
 - control of voltages
 - automatic correction (minimise figure / slope errors)
 - defocus beam to given size / shape
 - ☀ Active research:
 - bend mirror to given ellipse
 - create non-Gaussian beam profile (e.g. top-hat intensity)
- Ease of use for beamline teams and users

Old type bimorph mirrors

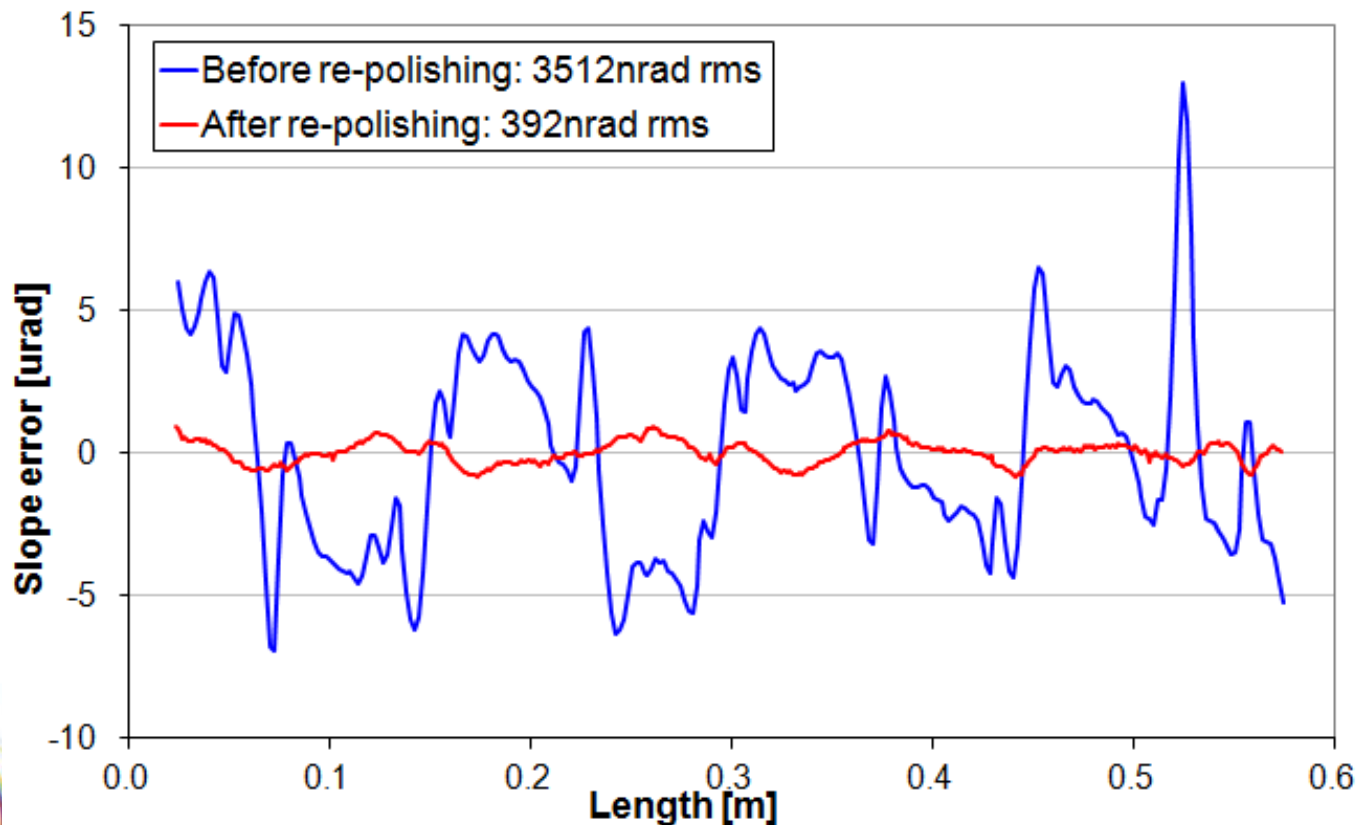
- ☀ Complicated internal structure
- ☀ Major problems caused by junction effect [1]



[1] S. G. Alcock, J. P. Sutter, K. J. S. Sawhney, D. R. Hall, K. McAuley, and T. Sorensen, "Bimorph mirrors: The Good, the Bad, and the Ugly," Nuclear Instruments and Methods A, vol. 710, pp. 87–92, May 2013

Junction effect

- ☀ Junction effect removed by repolishing
 - 6 bimorphs successfully repolished + 1 being repolished
 - Much improved slope errors (factor of 10) to below 500nrad
 - **Significantly** improved size & profile of reflected X-ray beam

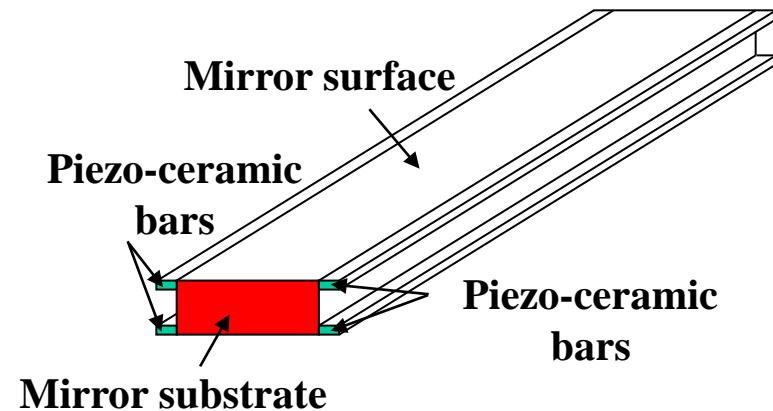
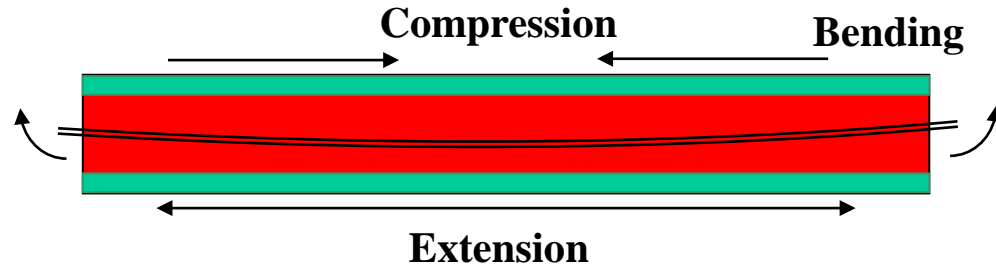


Next generation bimorph mirrors

☀️ New design: piezo ceramics glued to side of substrate [2]

- ✓ Eliminates junction effect
- ✓ Less expensive
- ✓ Simpler design
- ✓ Can be super-polished / ion beam figured
- ✓ Simple substrate can be 'bimorphized'
- ✗ Less responsive → reduced range of bending (?)

[2] Patent 1000471-05/02/2010



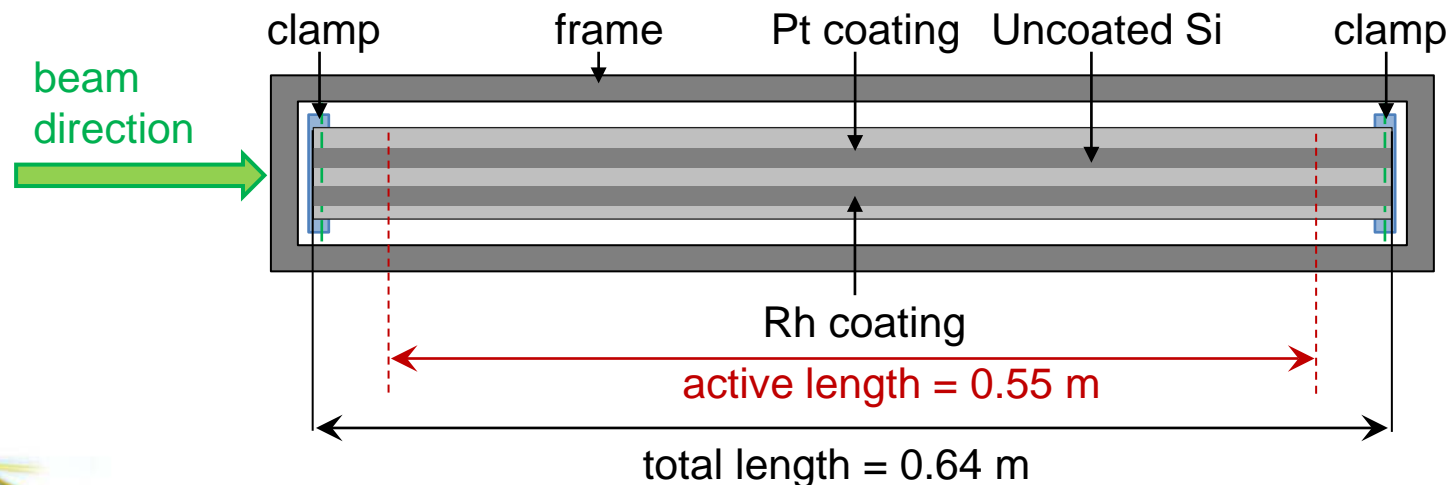
Diagrams courtesy of Thales -SESO

DLS Next Generation bimorph mirror

☀ Manufacturer: Thales-SESO

☀ Characteristics:

- Designed to be used on a range of beamlines
- Versatile mounting (facing up, down and sideways)
- 3 active regions: Rh & Pt coating + uncoated Si (central)
- 16 electrodes



Ex-situ metrology

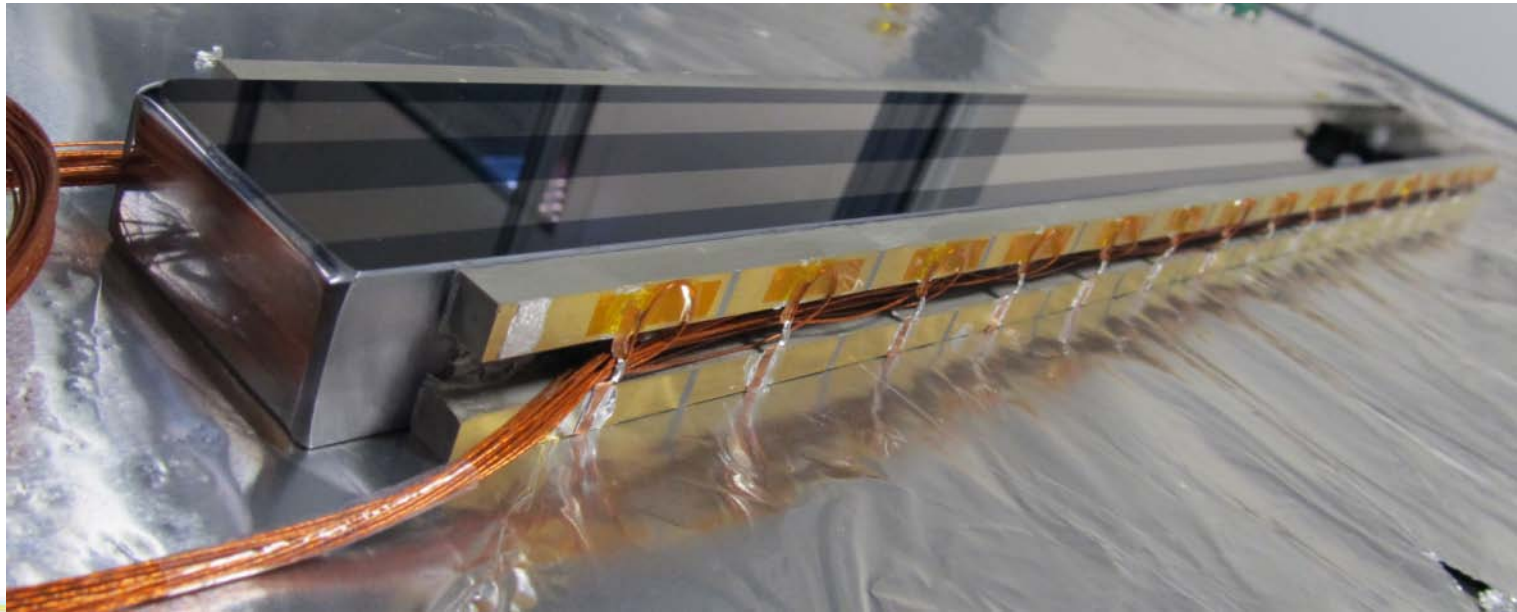
- ☀ Diamond-NOM: non contact, slope measuring profiler [3]
- ☀ Optical surface facing upwards
- ☀ Automated & integrated voltage control & Diamond-NOM scans (EPICS)



[3] S. G. Alcock, K. J. S. Sawhney, S. Scott, U. Pedersen, R. Walton, F. Siewert, T. Zeschke, F. Senf, T. Noll, and H. Lammert, "The Diamond-NOM: a non-contact profiler capable of characterizing optical figure error with sub-nm repeatability", Nucl. Instr. and Meth. A, Volume 616, Issue 2-3, p. 224-228 (2010)

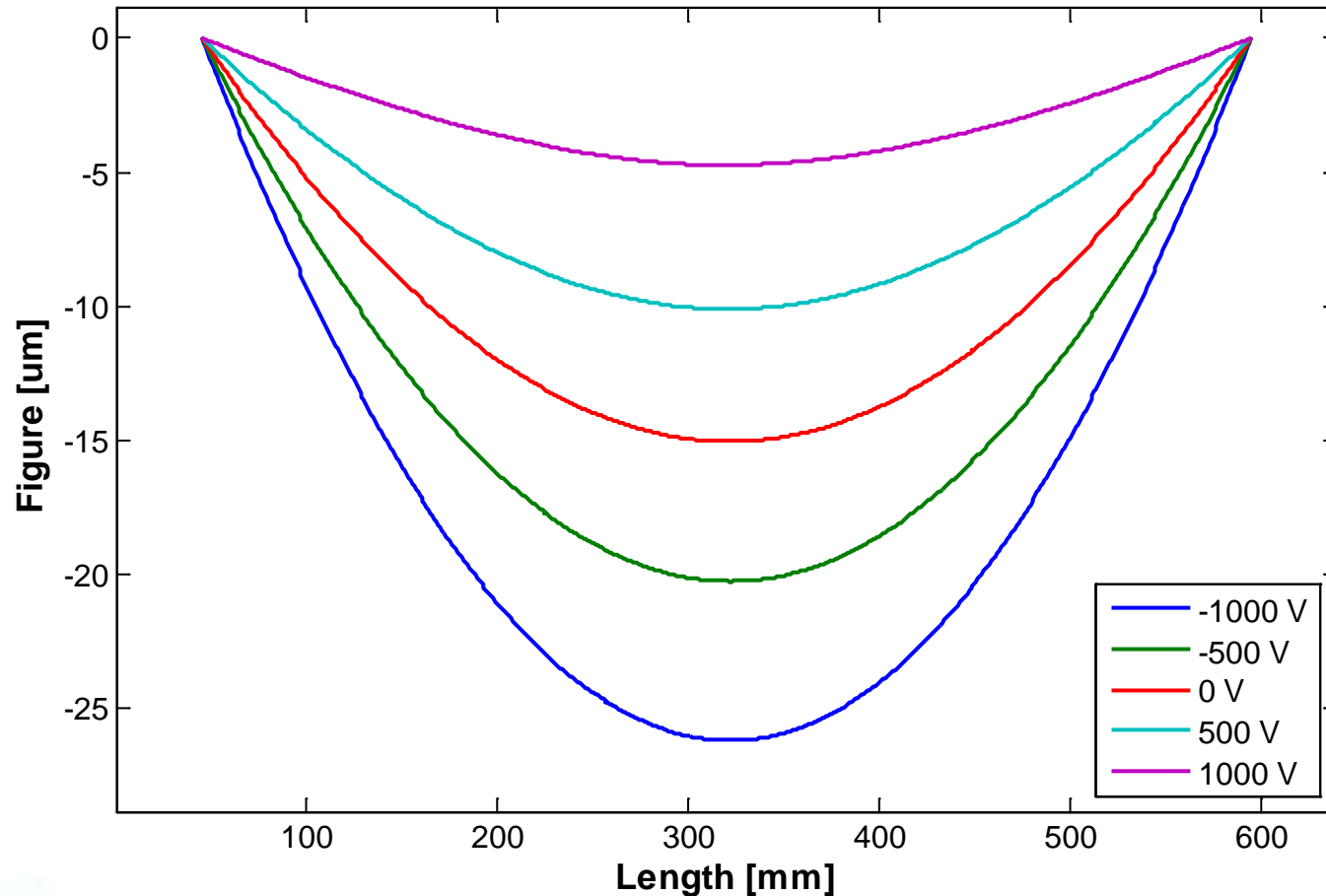
Metrology characterisation

- ☀ Bending range of mirror
- ☀ Stability of curvature
- ☀ Piezo response functions (PRFs)
- ☀ Optimisation of slope error using matrix correction method



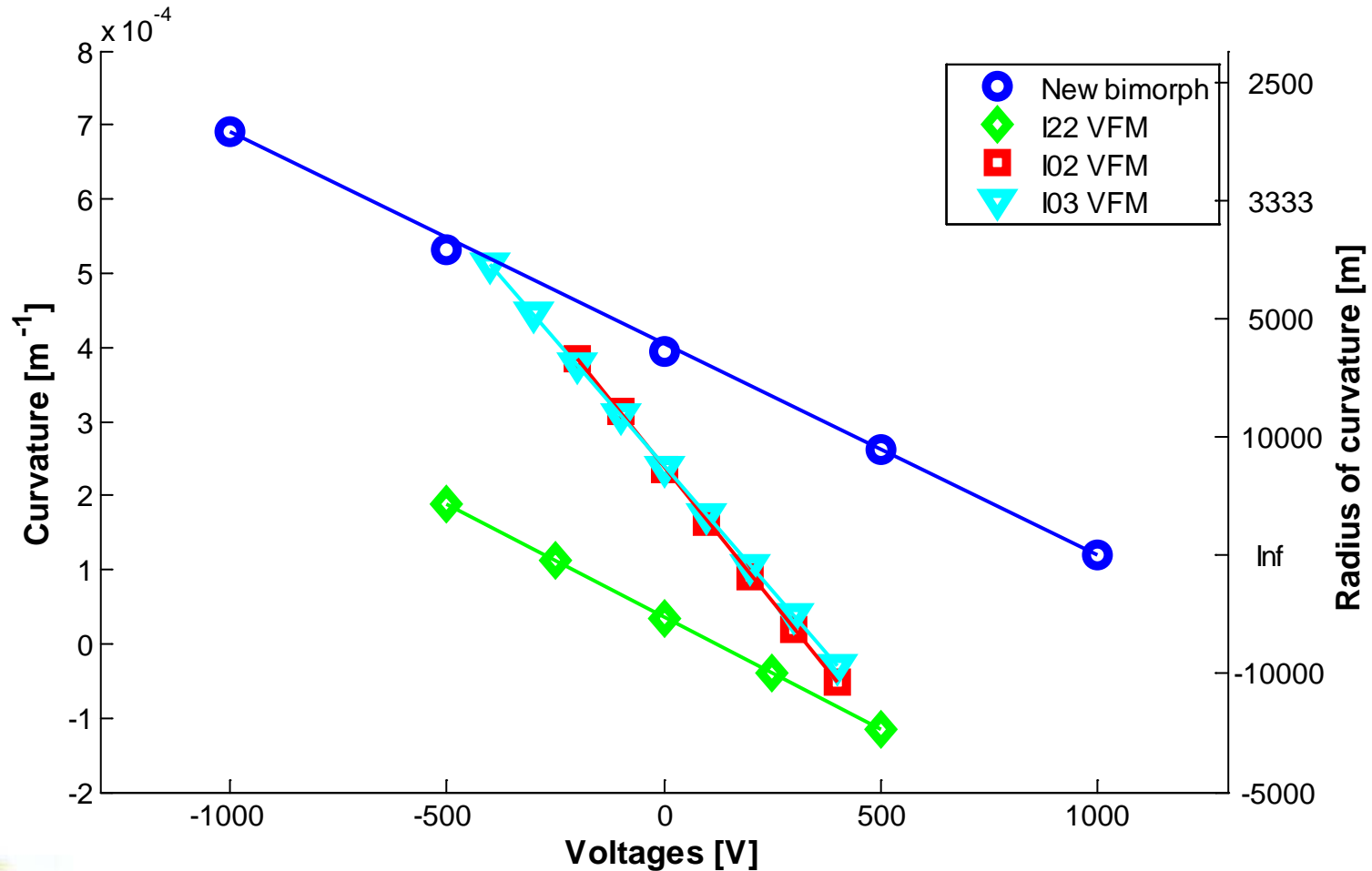
Bending tests

☀ Radius of curvature: flat (+1300V) to ~1430 m (-1000 V)



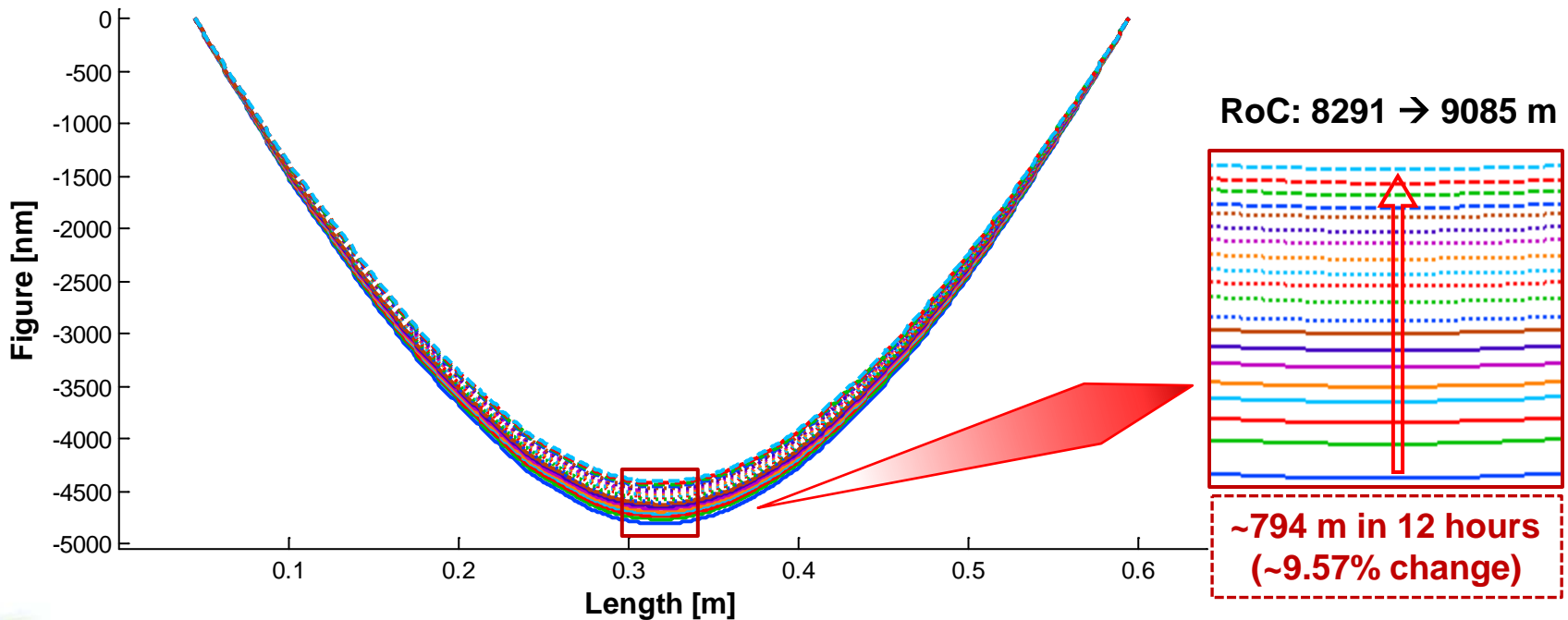
Dynamic range of bending

- ☀ Range of bending comparable to thicker, old type bimorphs



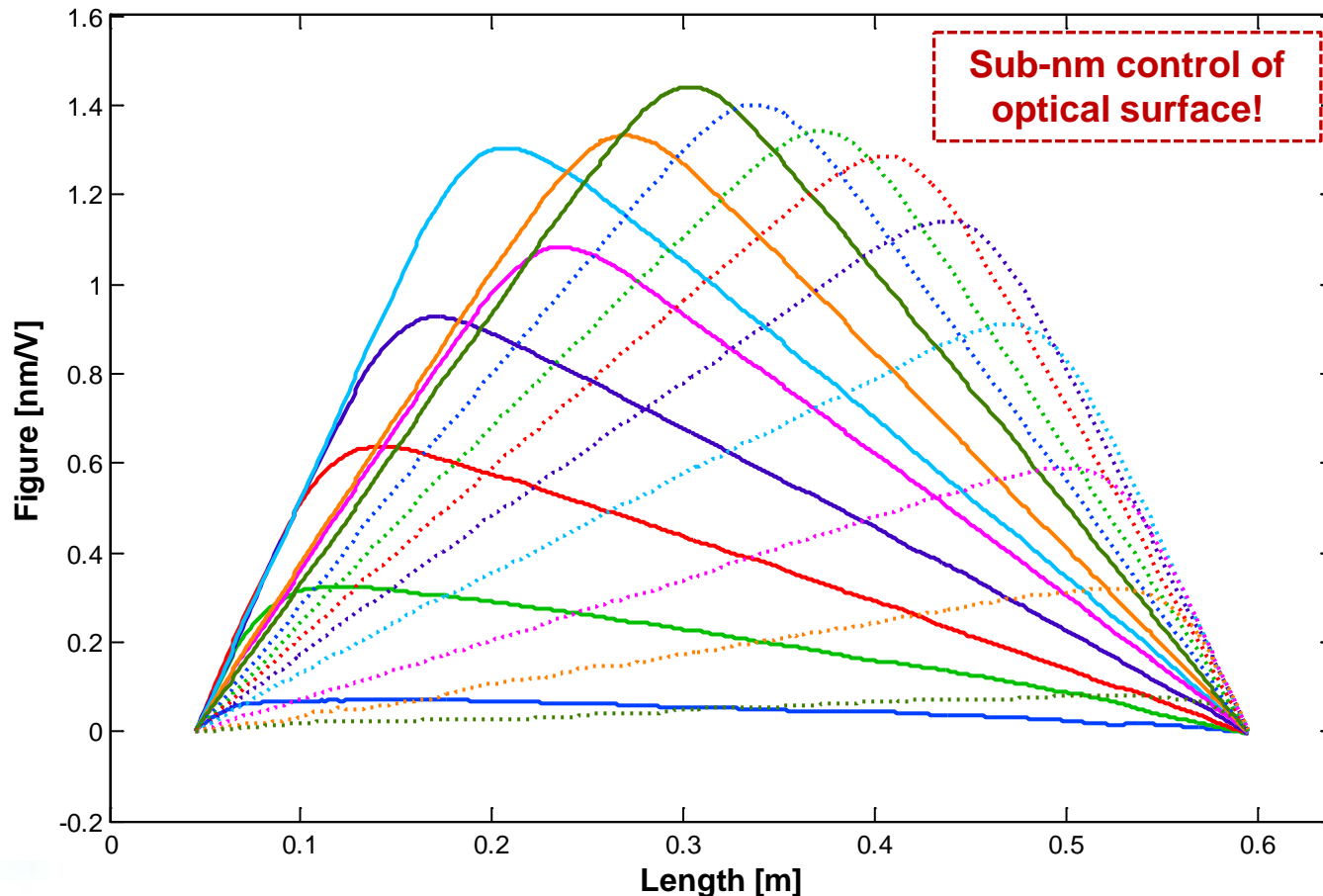
Stability tests

- ☀ Monitor curvature over several days at flattest (+1000 V) & most concave situations (-1000 V)
- ☀ Significant drift (~10%): piezos overcoming friction from holder



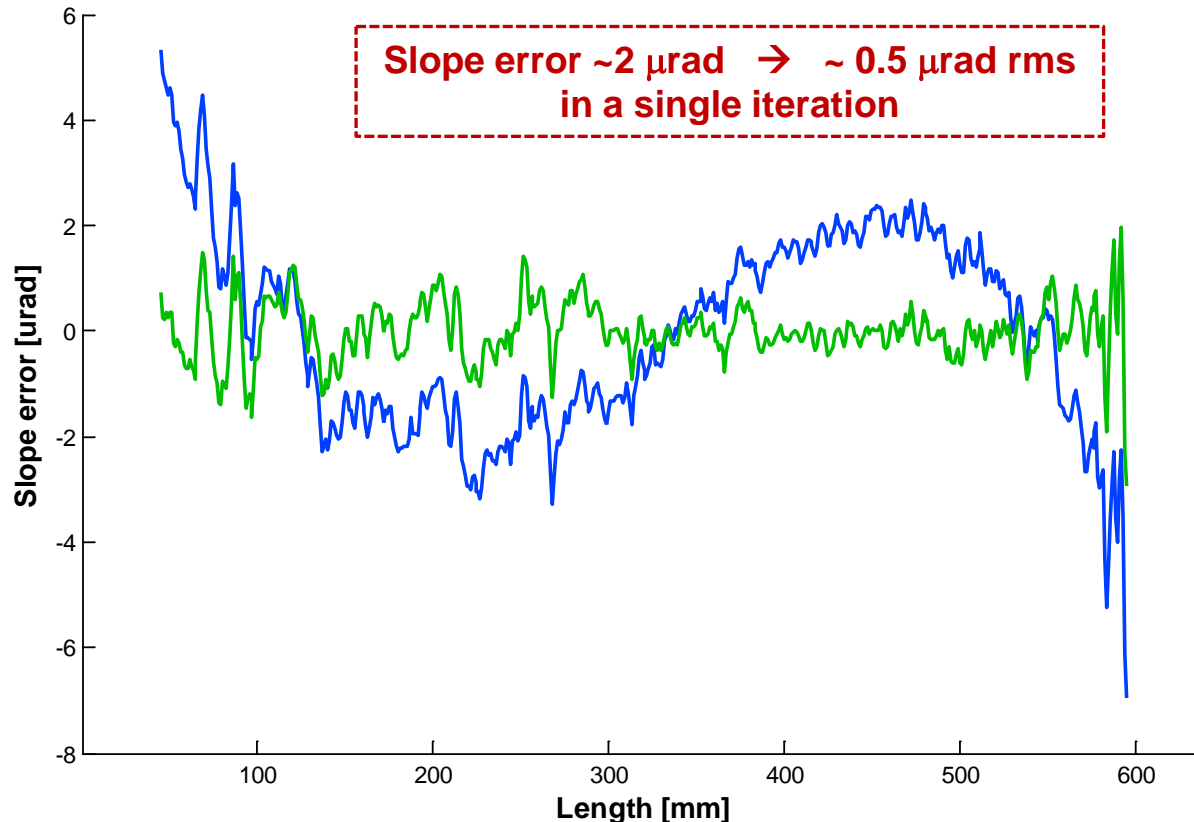
Piezo response functions

- ☀ Characterize how individual piezos respond to applied voltage



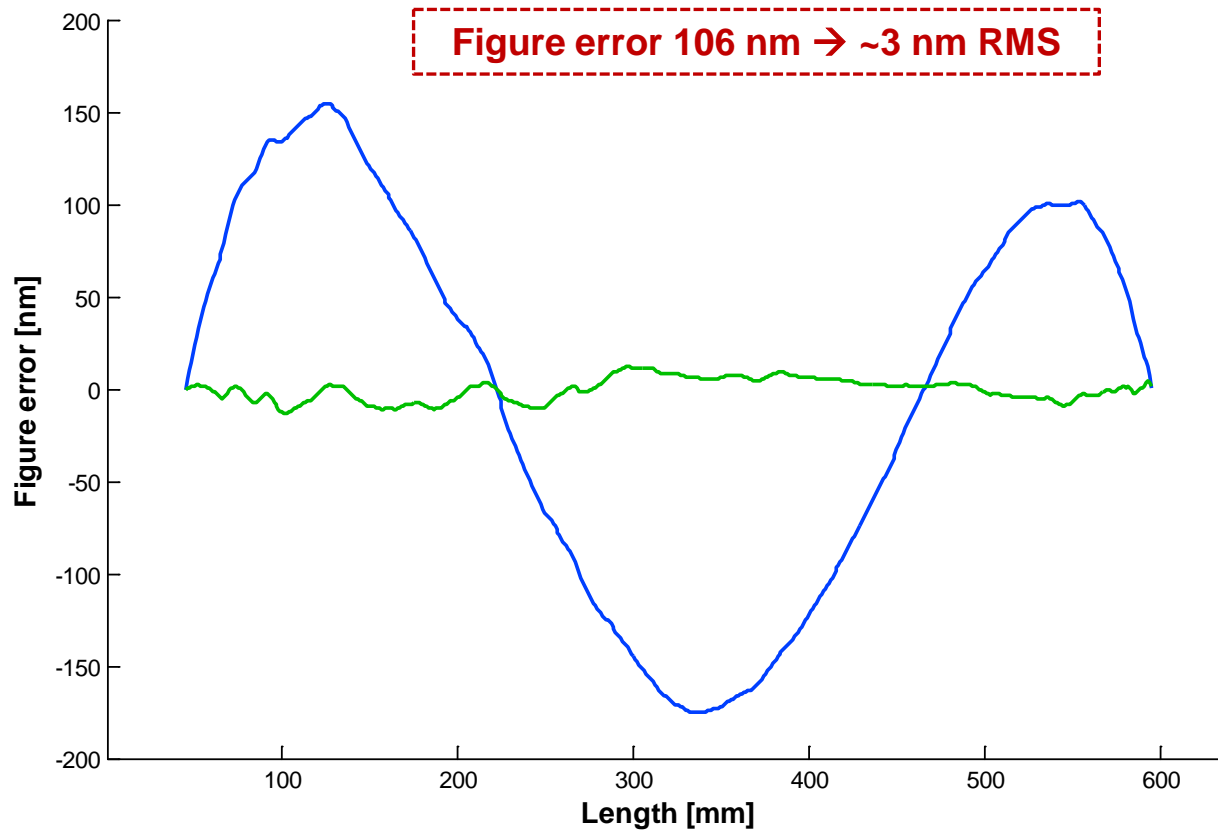
Matrix optimisation

- ☀ Correction voltages obtained by inverse matrix method
- ☀ Remaining slope error due to polishing defects



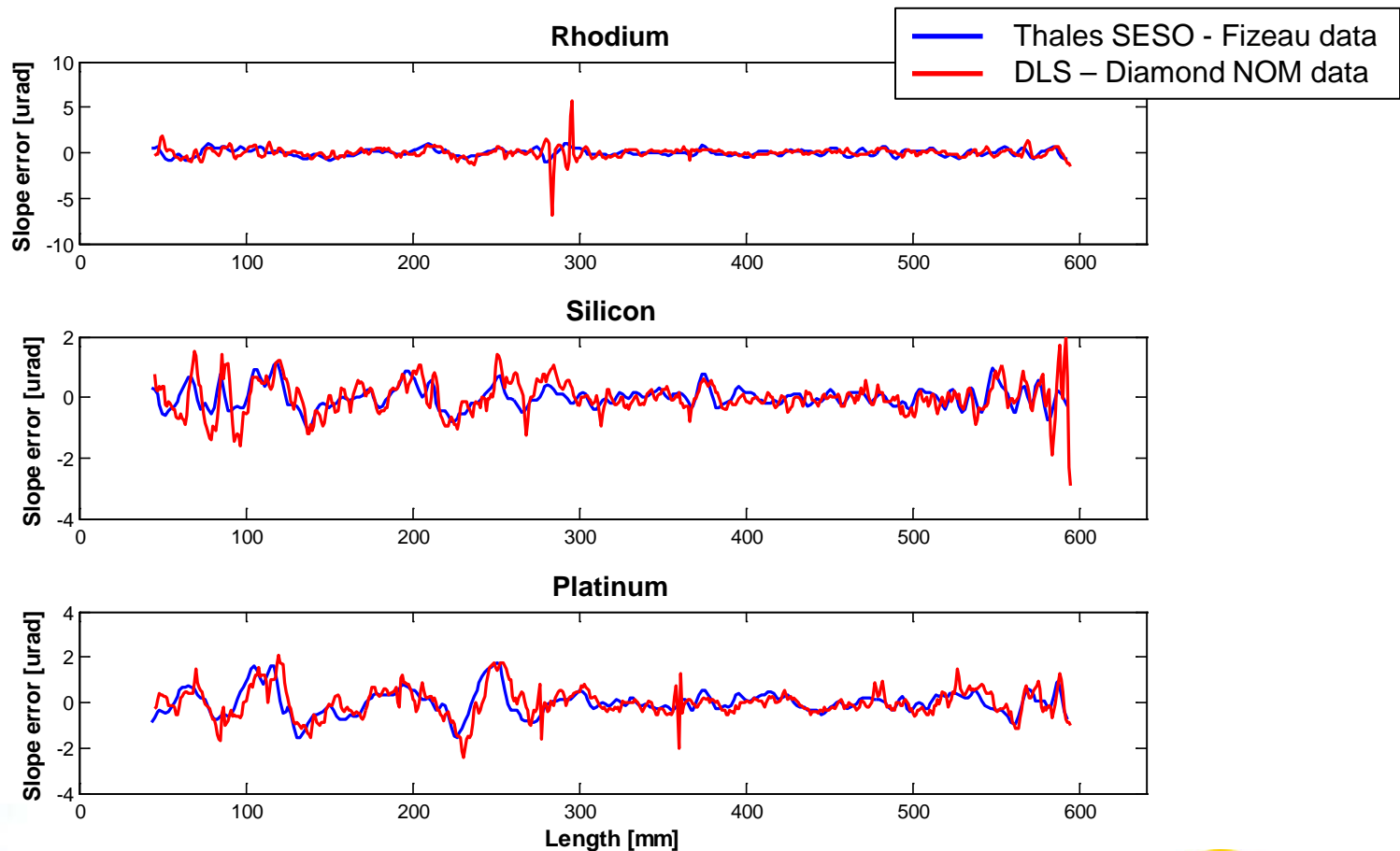
Matrix optimisation

- ☀ Improvement to figure error over central, uncoated Si stripe



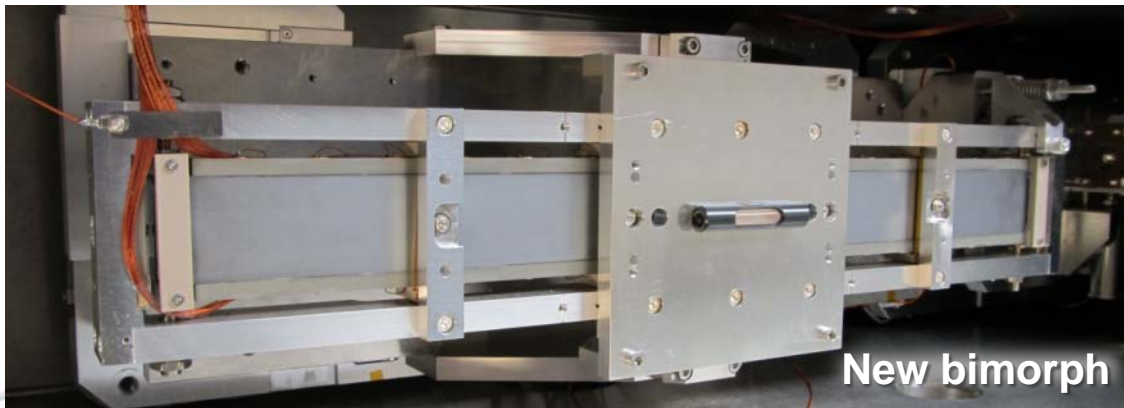
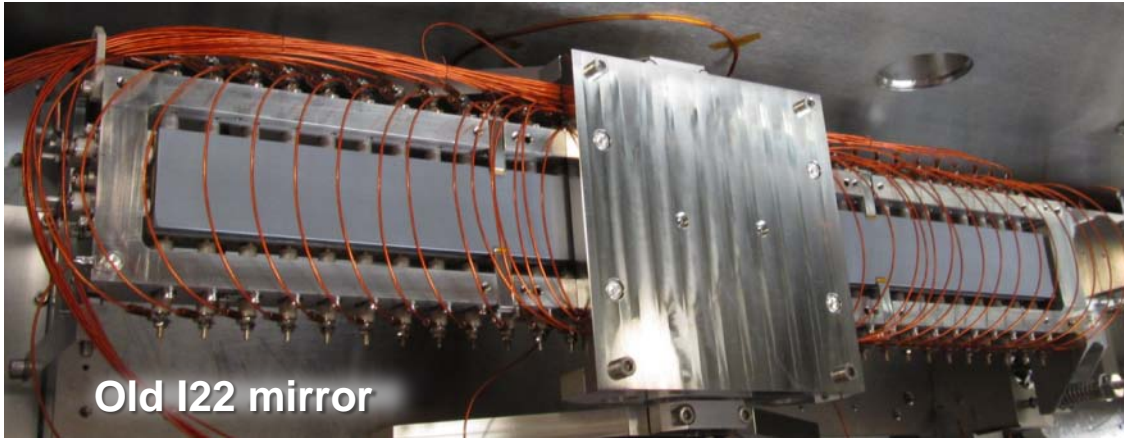
Agreement with Thales-SESO data

- 🌟 Diamond-NOM optimised slope error vs. Thales SESO slope error (high order polynomial removed)



Beamline installation

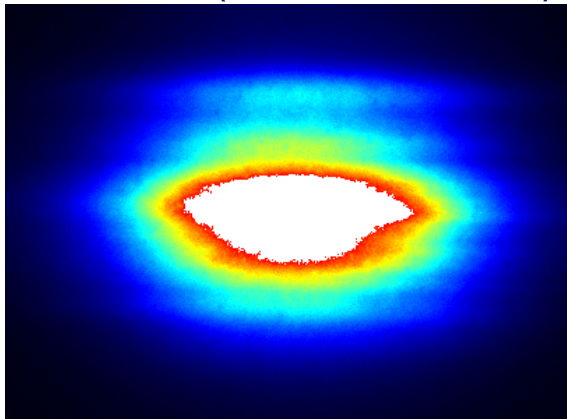
- ☀ New type bimorph mirror installed on I22 (June 2013)



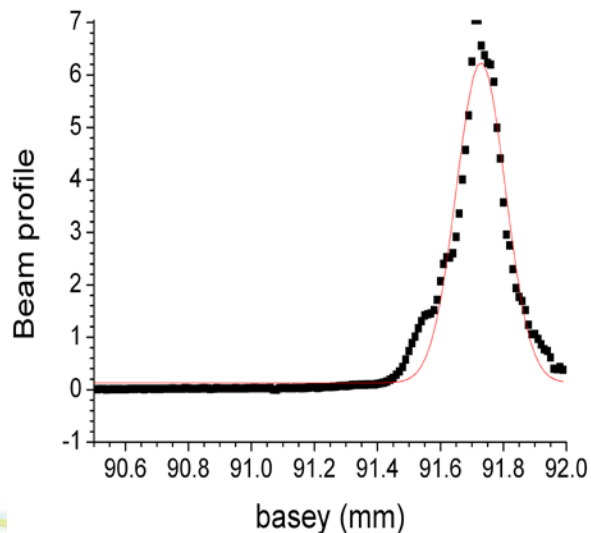
Acknowledgements to I22 team: Nick Terrill, Lee Davidson, Marc Malfois, Olga Shebanova & Andy Smith

In-situ X-ray metrology

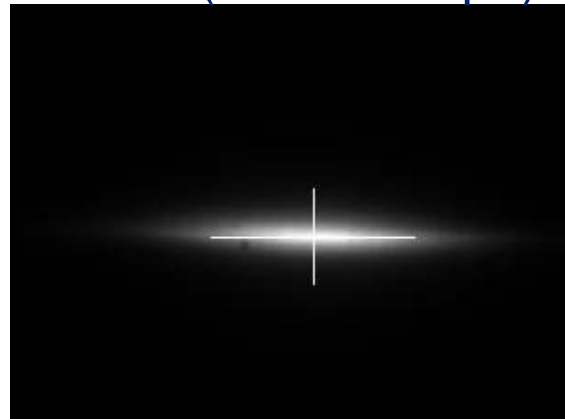
'Before' (old I22 mirror)



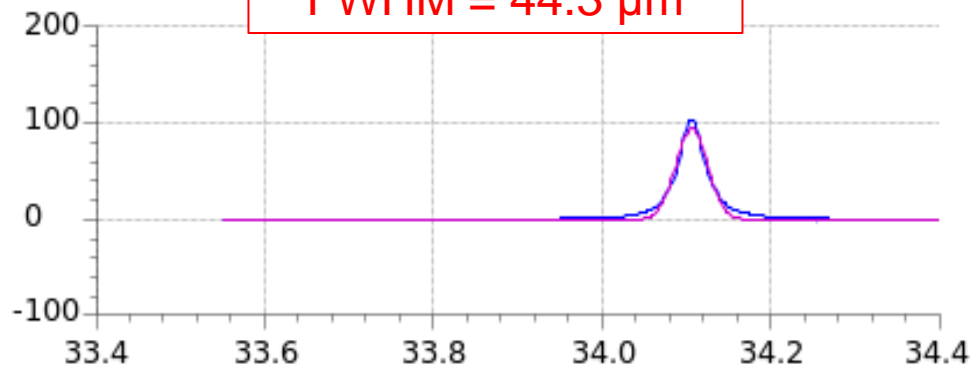
FWHM = 183 μm



'After' (new bimorph)



FWHM = 44.3 μm



- ☀ Focusing performance hasn't degraded over 4 months of beamline operation

Data courtesy of John Sutter (Optics Group) and I22 team

Conclusions

- ☀ DLS Next Generation bimorph mirror achieves ~ 0.5 urad slope error over a bending range of flat to 1.4 km (concave)
- ☀ Problems with holder, and ultimate performance limited by polishing issues (damage during fabrication)
- ☀ Successfully replaced old type bimorph mirror on beamline
→ **significant** improvement to beamline performance
- ☀ Perspectives:
 - New design needed for holder
 - Possibility of super-polishing substrates

Thank you for your attention

